

## United States Patent and Trademark Office

en

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/466,828	12/20/1999	SHUNPEI YAMAZAKI	0756-2077	1635	
31780 ERIC ROBINS	7590 10/26/2007 ON		EXAMINER		
PMB 955			NGO, NGAN V		
21010 SOUTH			ART UNIT	PAPER NUMBER	
POTOMAC FALLS, VA 20165			2818		
			MAIL DATE	DELIVERY MODE	
			10/26/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)			
Office Action Commons	09/466,828	YAMAZAKI ET AL.			
Office Action Summary	Examiner	Art Unit			
	Ngan Ngo	2818			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the o	correspondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period w  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION  B6(a). In no event, however, may a reply be ting  ATE OF THIS COMMUNICATION  B6(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, may a reply be ting  B7(a). In no event, however, however, may a reply be ting  B7(a). In no event, however, howe	N.  mely filed  n the mailing date of this communication.  ED (35 U.S.C. § 133).			
Status					
1)⊠ Responsive to communication(s) filed on 23 Au	iaust 2007				
	action is non-final.				
3) Since this application is in condition for allowar		osecution as to the merits is			
closed in accordance with the practice under E	•				
Disposition of Claims	, , , , , , , , , , , , , , , , , , , ,				
4)⊠ Claim(s) <u>1-42</u> is/are pending in the application.	•				
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-42</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or	election requirement.				
Application Papers					
9) The specification is objected to by the Examine	r				
10) The drawing(s) filed on is/are: a) acce		Examiner			
Applicant may not request that any objection to the					
Replacement drawing sheet(s) including the correcti					
11) ☐ The oath or declaration is objected to by the Ex		-			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a	)-(d) or (f).			
a) ☐ All b) ☐ Some * c) ☐ None of:					
1. Certified copies of the priority documents have been received.					
2. Certified copies of the priority documents have been received in Application No					
<ol><li>Copies of the certified copies of the prior</li></ol>	ity documents have been receive	ed in this National Stage			
application from the International Bureau	(PCT Rule 17.2(a)).	•			
* See the attached detailed Office action for a list of	of the certified copies not receive	ed.			
Attachment(s)					
1) Notice of References Cited (PTO-892)	4) Interview Summary	(PTO-413)			
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D	ate			
3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	5)  Notice of Informal F 6)  Other:	atent Application .			

09/466,828 Art Unit: 2818

The amendment filed June 25, 2007 has been entered and made of record as paper no. 0607.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1, 2, 4-8, 10, 12-14, 16-18, 20-27, 29, 31-33, 35, and 36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Troxell et al (US 4,851,363, of record) in view of Mimura et al (US 4,954,855).

Troxell discloses a method and a device comprising a silicon oxide insulating film (24,26, and 28) over a glass substrate (10) and a crystalline semiconductor island (100, 101, and 102). Since the silicon oxide insulating film does not have halogen and carbon (which are about zero), it is clear that the insulating film (24,26, and 28) have halogen at a concentration less than 5 x 10<sup>20</sup> cm<sup>-3</sup> and carbon at a concentration less than 5 x 10<sup>19</sup> cm<sup>-3</sup>. Mimura et al further teach that silicon oxide can be made by plasma CVD. Note lines 50-53, column 5 of Mimura et al. Therefore it would have been obvious to one of ordinary skill in the art to form the silicon oxide by plasma CVD as taught by Mimura in Troxell's device.

In re claim 25, Troxell shows the interlayer (35,36)

Claims 3, 9, 11, 15, 19, 28, 30, 34, and 37-42 are rejected under 35 U.S.C. 103(a) as being unpatentable over Troxell et al (US 4851363) in view of Mimura et al (US 4,954,855) as applied to claims 1, 2, 4-8, 10, 12-14, 16-18, 20-27, 29, 31-33,

09/466,828

Art Unit: 2818

35, and 36 above, and further in view of Tamai et al (US 5506064) and Inushima et al (US 5629245).

Troxell discloses all the subject matter discussed above. Tamai further teaches that carbon can be detected by second ion mass spectroscopy. Note lines 12 to 15, column 3 of Tamai. Inushima further teaches that insulating film can be formed by plasma CVD using an organic silane. Note lines 46-51, column 3 of Inushima et al. Therefore, it would have been obvious to one of ordinary skill in the art to use the teachings of Troxell, Mimura, Tamai, and Inushima to form the claimed method and device.

Any inquiry concerning this communication should be directed to Examiner Ngan Ngo at telephone number (571) 272-1711. The fax phone number for the organization where this application or proceeding is assigned is (571)-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Application/Control Number: 09/466,828 Art Unit: 2818

Page 4

Ngan Van Ngo Primary Examiner

Ngan Ngo

October 24, 2007